

In a position detecting system and method, an electron beam is irradiated to a sample including a portion to be measured, and the electron beam is caused to move in relation to the portion to be measured in the sample. Furthermore, a voltage is applied to the sample which is scanned by the electron beam, and a current flowing in the sample because of the applied voltage, is detected. Thus, the position of the portion to be measured can be determined from a scanning start position of the electron beam and the position where the detected current changes.